

EV0773 446 #6

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. 09/834,660

Filing Date. April 12, 2001

Inventor. Luan C. Tran

Assignee. Micron Technology, Inc.

Group Art Unit. 2813

Examiner. Laura M. Schillinger

Attorney's Docket No. MI22-1637

Title: Semiconductor Processing Methods Of Forming Transistors, Semiconductor Processing Methods Of Forming Dynamic Random Access Memory Circuitry, And Related Integrated Circuitry

INFORMATION DISCLOSURE STATEMENT

Reference - - See attached Form PTO-1449

In compliance with 37 C.F.R. §§ 1.56, 1.97 and 1.98, your attention is directed to the reference listed on the attached Form PTO-1449. No admission is made regarding whether the submitted reference is prior art.

Citation of this reference is respectfully requested.

Respectfully submitted,

Date: Apr. 30, 2002

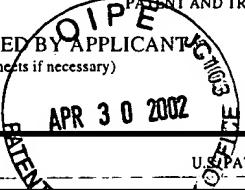

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Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE			ATTY. DOCKET NO. MI22-1637	SERIAL NO. 09/834,660
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)					APPLICANT Luan C. Tran	
					FILING DATE 04/12/01	GROUP 2813
U.S. PATENT DOCUMENTS						
*Examiner Initial		Document Number	Date	Name	Class	Subclass
	AA					
	AB					
	AC					
	AD					
	AE					
	AF					
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	AH					
	AI					
	AJ					
	AK					
FOREIGN PATENT DOCUMENTS						
		Document Number	Date	Country	Class	Subclass
	AL					
	AM					
	AN					
	AO					
	AP					
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)						
	AR		S. Wolf, <i>Silicon Processing for the VLSI Era</i> , Volume 3 - The Submicron MOSFET, ©1995 Lattice Press, pages 330, 331, 366 and 367.			
	AS					
	AT					
EXAMINER			DATE CONSIDERED			
<p>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</p>						